

Tool ID: 505
Tool Location: 122

Equipment Information Sheet JEOL 9500

Manager: Alan R. Bleier
Backup: Roberto Panepucci
Backup: John Treichler

607-254-4931
607-254-4855
607-254-4949

Calls to staff phones will be automatically forwarded to their cell phones during accessible hours. At other times leave a message or send them an email.

SAFETY

No safety concerns during normal operation

USAGE RESTRICTIONS

No buddy system restrictions imposed on normal operation.

Please review electron beam lithography training materials, in AFS, at shares - public - processes_from_cnf_staff - ElectronBeamLithography - TrainingMaterials (accessible on any general use PC or CNF Thin client at CNF)

SCHEDULING/SIGN-UP RESTRICTIONS

Minimum Tool Time: 30 minutes

- Please put the beam current you plan to use in the Process field in Coral when you make the reservation.
- No more than 3 hour reservation between the hours of 8am - 8pm, Monday through Friday.
- Maximum 12 hours reserved in advance at any time per person.
- The same user, group, or company must have at least 3 hours between any 2 reservations.

MATERIALS COMPATIBILITY CATEGORY

Tool Category 5: Class A and B Metals and Compounds

Allowed	Not Allowed
Tool category 1/1E, 2, 3, and 4 materials	
Silicon Based Substrates and Films	
III/V compound Semiconductors	
Glass Substrates	
PECVD and ALD Films	
Cured organics and baked Photoresist	
CNF Class A, B, and Refractory metals	
Exposed Gold, Silver, Copper	
Alkali and Alkaline Compounds	
Organic/Biology Molecules prepared-w/salt buffers	
High Vapor Pressure Materials (Mg, Ca, Zn)*	* Some tool restrictions on high vapor pressure materials may apply
Soft organic materials	

High Vapor Pressure Metals and Compounds are materials that have a vapor pressure above 1e-6 Torr at 400 C.

Additional Material Restrictions and Exceptions

- Fully baked resists only; do not load samples with unbaked resist or glue or anything that may degas.
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Last Updated: 03/27/2024